

Title (en)  
INDIUM ELECTROPLATING BATHS FOR THIN LAYER DEPOSITION

Title (de)  
INDIUM-ELEKTROPLATTIERUNGSBÄDER ZUR DÜNNSCHICHTABSCHEIDUNG

Title (fr)  
BAINS D'ÉLECTRODÉPOSITION À L'INDIUM POUR DÉPÔT DE COUCHE MINCE

Publication  
**EP 2245216 A1 20101103 (EN)**

Application  
**EP 09706296 A 20090128**

Priority

- US 2009032291 W 20090128
- US 2211308 A 20080129

Abstract (en)  
[origin: US2009188808A1] Indium (In) electroplating solutions which are used to deposit compositionally pure, uniform, substantially defect free and smooth In films with near 100% plating efficiency and repeatability. In one embodiment the plating solution includes an In source, citric acid and its conjugate pair salt and a solvent. At a pH value of below 4.0, sub-micron thick In layers with close to 100% purity at close to 100% plating efficiency are produced. Such In layers are used in fabrication of electronic devices such as thin film solar cells.

IPC 8 full level  
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Cited by  
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**US 2211308 A 20080129**; EP 09706296 A 20090128; TW 98103278 A 20090202; US 2009032291 W 20090128